

UNITED STATES PATENT AND TRADEMARK OFFICE

INITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

NOTICE OF ALLOWANCE AND FEE(S) DUE

23483 7590 10/10/2012 WILMERHALE/BOSTON 60 STATE STREET BOSTON, MA 02109

EXAMINER	
CHEN, BRET P	

ART UNIT PAPER NUMBER

1715

DATE MAILED: 10/10/2012

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
12/407,556	03/19/2009	Roy G. Gordon	42697.135-US7	7572	

TITLE OF INVENTION: VAPOR DEPOSITION OF METAL OXIDES, SILICATES AND PHOSPHATES, AND SILICON DIOXIDE

APPLN. TYPE	SMALL ENTITY	ISSUE FEE DUE	PUBLICATION FEE DUE	PREV. PAID ISSUE FEE	TOTAL FEE(S) DUE	DATE DUE
nonprovisional	YES	\$885	\$300	\$O	\$1185	01/10/2013

THE APPLICATION IDENTIFIED ABOVE HAS BEEN EXAMINED AND IS ALLOWED FOR ISSUANCE AS A PATENT. <u>PROSECUTION ON THE MERITS IS CLOSED</u>. THIS NOTICE OF ALLOWANCE IS NOT A GRANT OF PATENT RIGHTS. THIS APPLICATION IS SUBJECT TO WITHDRAWAL FROM ISSUE AT THE INITIATIVE OF THE OFFICE OR UPON PETITION BY THE APPLICANT. SEE 37 CFR 1.313 AND MPEP 1308.

THE ISSUE FEE AND PUBLICATION FEE (IF REQUIRED) MUST BE PAID WITHIN <u>THREE MONTHS</u> FROM THE MAILING DATE OF THIS NOTICE OR THIS APPLICATION SHALL BE REGARDED AS ABANDONED. <u>THIS STATUTORY PERIOD CANNOT BE EXTENDED</u>. SEE 35 U.S.C. 151. THE ISSUE FEE DUE INDICATED ABOVE DOES NOT REFLECT A CREDIT FOR ANY PREVIOUSLY PAID ISSUE FEE IN THIS APPLICATION. IF AN ISSUE FEE HAS PREVIOUSLY BEEN PAID IN THIS APPLICATION (AS SHOWN ABOVE), THE RETURN OF PART B OF THIS FORM WILL BE CONSIDERED A REQUEST TO REAPPLY THE PREVIOUSLY PAID ISSUE FEE TOWARD THE ISSUE FEE NOW DUE.

HOW TO REPLY TO THIS NOTICE:

I. Review the SMALL ENTITY status shown above.

If the SMALL ENTITY is shown as YES, verify your current SMALL ENTITY status:	If the SMALL ENTITY is shown as NO:
A. If the status is the same, pay the TOTAL FEE(S) DUE shown above.	A. Pay TOTAL FEE(S) DUE shown above, or
B. If the status above is to be removed, check box 5b on Part B - Fee(s) Transmittal and pay the PUBLICATION FEE (if required) and twice the amount of the ISSUE FEE shown above, or	B. If applicant claimed SMALL ENTITY status before, or is now claiming SMALL ENTITY status, check box 5a on Part B - Fee(s) Transmittal and pay the PUBLICATION FEE (if required) and 1/2 the ISSUE FEE shown above.

II. PART B - FEE(S) TRANSMITTAL, or its equivalent, must be completed and returned to the United States Patent and Trademark Office (USPTO) with your ISSUE FEE and PUBLICATION FEE (if required). If you are charging the fee(s) to your deposit account, section "4b" of Part B - Fee(s) Transmittal should be completed and an extra copy of the form should be submitted. If an equivalent of Part B is filed, a request to reapply a previously paid issue fee must be clearly made, and delays in processing may occur due to the difficulty in recognizing the paper as an equivalent of Part B.

III. All communications regarding this application must give the application number. Please direct all communications prior to issuance to Mail Stop ISSUE FEE unless advised to the contrary.

IMPORTANT REMINDER: Utility patents issuing on applications filed on or after Dec. 12, 1980 may require payment of maintenance fees. It is patentee's responsibility to ensure timely payment of maintenance fees when due.

Page 1 of 3

PART B - FEE(S) TRANSMITTAL

Complete and send this form, together with applicable fee(s), to: <u>Mail</u> Mail Stop ISSUE FEE Commissioner for Patents P.O. Box 1450 1450

or <u>Fax</u>	Alexandria, Virginia 22313- (571)-273-2885
---------------	---

INSTRUCTIONS: This appropriate. All further indicated unless correctu maintenance fee notifica	ed below or directed oth	or trans ig the I ierwise	smitting the ISSU Patent, advance of in Block 1, by (a	UE FEE and PUBLIC rders and notification a) specifying a new c	CATI of n	ON FEE (if requir naintenance fees wi pondence address;	ed). B 11 be 1 and/or	Blocks 1 through 5 sh mailed to the current (b) indicating a sepa	ould be completed where correspondence address as rate "FEE ADDRESS" for
CURRENT CORRESPONDENCE ADDRESS (Note: Use Block 1 for any change of address) 23483 7590 10/10/2012 WILMERHALE/BOSTON 60 STATE STREET BOSTON, MA 02109					Fee(pape have	s) Transmittal. This rs. Each additional its own certificate (Certi	certif paper, of mai	cate cannot be used for , such as an assignmen ling or transmission.	domestic mailings of the or any other accompanying at or formal drawing, must nission deposited with the United t class mail in an envelope above, or being facsimile te indicated below. (Depositor's name)
									(Signature)
									(Date)
APPLICATION NO.	FILING DATE			FIRST NAMED INVEN	JTOR		ATTO	RNEY DOCKET NO.	CONFIRMATION NO.
12/407,556	03/19/2009			Roy G. Gordon		I	4	2697.135-US7	7572
TITLE OF INVENTION	SMALL ENTITY		ETAL OXIDES, S	SILICATES AND PH		HATES, AND SILI		DIOXIDE TOTAL FEE(S) DUE	DATE DUE
		153		\$300	JUE	\$0	FEE	\$1185	01/10/2013
nonprovisional YES \$885 EXAMINER ART UNI			ART UNIT	\$500 CLASS-SUBCLAS	s	90		\$1165	01/10/2013
CHEN, BRET P 1715 427-255310									
 "Fee Address" ind PTO/SB/47; Rev 03-0 Number is required. ASSIGNEE NAME A 	ND RESIDENCE DATA less an assignee is ident h in 37 CFR 3.11. Comp	" Indica ed. Use A TO B	tion form of a Customer E PRINTED ON T	or agents OR, alter (2) the name of a registered attorney 2 registered patent listed, no name wi	rnativ single y or a t attor ill be or typ or typ the pa g an a	 firm (having as a i gent) and the name neys or agents. If n printed. e) tent. If an assignetissignment. 	membo s of uj o nam e is id	lentified below, the do	cument has been filed for
Please check the appropr	iate assignee category or	catego	ries (will not be pr	rinted on the patent):		Individual 🗖 Cor	porati	on or other private gro	up entity D Government
 4a. The following fee(s) Issue Fee Publication Fee (N Advance Order - # 	to small entity discount p	permitte		A check is enclosed Payment by cred The Director is h	sed. it caro ereby	1. Form PTO-2038 i	is attac	required fee(s), any del	
	s SMALL ENTITY stat	is. See î	37 CFR 1.27.	11				TITY status. See 37 CF	
NOTE: The Issue Fee an interest as shown by the	d Publication Fee (if req records of the United Sta	uired) w tes Pate	vill not be accepteent and Trademark	d from anyone other t c Office.	han th	e applicant; a regis	tered a	attorney or agent; or th	e assignee or other party in
Authorized Signature						Date			
	e					0			
This collection of inform an application. Confiden submitting the complete this form and/or suggesti Box 1450, Alexandria, V Alexandria, Virginia 223 Under the Paperwork Re	tiality is governed by 35 d application form to the lons for reducing this bu /irginia 22313-1450. DO 13-1450.	U.S.C. USPT rden, sh NOT S	122 and 37 CFR O. Time will vary ould be sent to th SEND FEES OR O	1.14. This collection depending upon the e Chief Information C COMPLETED FORM	is esti indiv Office IS TC	mated to take 12 m idual case. Any con r, U.S. Patent and T r THIS ADDRESS.	inutes nment Traden SENI	to complete, including s on the amount of tim nark Office, U.S. Depa O TO: Commissioner f	by the USPTO to process) g gathering, preparing, and he you require to complete rtment of Commerce, P.O. or Patents, P.O. Box 1450, number.

OMB 0651-0033

U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

	ted States Pate	NT AND TRADEMARK OFFICE	UNITED STATES DEPAR United States Patent and ' Address: COMMISSIONER F P. O. Box 1450 Alexandria, Virginia 223 www.uspto.gov	Frademark Office OR PATENTS
APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
12/407,556	03/19/2009	Roy G. Gordon	42697.135-US7	7572
23483 75	90 10/10/2012		EXAM	INER
WILMERHALE/ 60 STATE STREE			CHEN,	BRET P
BOSTON, MA 021			ART UNIT	PAPER NUMBER
			1715	
			DATE MAILED: 10/10/201	2

Determination of Patent Term Adjustment under 35 U.S.C. 154 (b)

(application filed on or after May 29, 2000)

The Patent Term Adjustment to date is 521 day(s). If the issue fee is paid on the date that is three months after the mailing date of this notice and the patent issues on the Tuesday before the date that is 28 weeks (six and a half months) after the mailing date of this notice, the Patent Term Adjustment will be 521 day(s).

If a Continued Prosecution Application (CPA) was filed in the above-identified application, the filing date that determines Patent Term Adjustment is the filing date of the most recent CPA.

Applicant will be able to obtain more detailed information by accessing the Patent Application Information Retrieval (PAIR) WEB site (http://pair.uspto.gov).

Any questions regarding the Patent Term Extension or Adjustment determination should be directed to the Office of Patent Legal Administration at (571)-272-7702. Questions relating to issue and publication fee payments should be directed to the Customer Service Center of the Office of Patent Publication at 1-(888)-786-0101 or (571)-272-4200.

Privacy Act Statement

The Privacy Act of 1974 (P.L. 93-579) requires that you be given certain information in connection with your submission of the attached form related to a patent application or patent. Accordingly, pursuant to the requirements of the Act, please be advised that: (1) the general authority for the collection of this information is 35 U.S.C. 2(b)(2); (2) furnishing of the information solicited is voluntary; and (3) the principal purpose for which the information is used by the U.S. Patent and Trademark Office is to process and/or examine your submission related to a patent application or patent. If you do not furnish the requested information, the U.S. Patent and Trademark Office may not be able to process and/or examine your submission, which may result in termination of proceedings or abandonment of the application or expiration of the patent.

The information provided by you in this form will be subject to the following routine uses:

- 1. The information on this form will be treated confidentially to the extent allowed under the Freedom of Information Act (5 U.S.C. 552) and the Privacy Act (5 U.S.C 552a). Records from this system of records may be disclosed to the Department of Justice to determine whether disclosure of these records is required by the Freedom of Information Act.
- 2. A record from this system of records may be disclosed, as a routine use, in the course of presenting evidence to a court, magistrate, or administrative tribunal, including disclosures to opposing counsel in the course of settlement negotiations.
- 3. A record in this system of records may be disclosed, as a routine use, to a Member of Congress submitting a request involving an individual, to whom the record pertains, when the individual has requested assistance from the Member with respect to the subject matter of the record.
- 4. A record in this system of records may be disclosed, as a routine use, to a contractor of the Agency having need for the information in order to perform a contract. Recipients of information shall be required to comply with the requirements of the Privacy Act of 1974, as amended, pursuant to 5 U.S.C. 552a(m).
- 5. A record related to an International Application filed under the Patent Cooperation Treaty in this system of records may be disclosed, as a routine use, to the International Bureau of the World Intellectual Property Organization, pursuant to the Patent Cooperation Treaty.
- 6. A record in this system of records may be disclosed, as a routine use, to another federal agency for purposes of National Security review (35 U.S.C. 181) and for review pursuant to the Atomic Energy Act (42 U.S.C. 218(c)).
- 7. A record from this system of records may be disclosed, as a routine use, to the Administrator, General Services, or his/her designee, during an inspection of records conducted by GSA as part of that agency's responsibility to recommend improvements in records management practices and programs, under authority of 44 U.S.C. 2904 and 2906. Such disclosure shall be made in accordance with the GSA regulations governing inspection of records for this purpose, and any other relevant (i.e., GSA or Commerce) directive. Such disclosure shall not be used to make determinations about individuals.
- 8. A record from this system of records may be disclosed, as a routine use, to the public after either publication of the application pursuant to 35 U.S.C. 122(b) or issuance of a patent pursuant to 35 U.S.C. 151. Further, a record may be disclosed, subject to the limitations of 37 CFR 1.14, as a routine use, to the public if the record was filed in an application which became abandoned or in which the proceedings were terminated and which application is referenced by either a published application, an application open to public inspection or an issued patent.
- 9. A record from this system of records may be disclosed, as a routine use, to a Federal, State, or local law enforcement agency, if the USPTO becomes aware of a violation or potential violation of law or regulation.

	Application No.	Applicant(s)							
	12/407,556	GORDON ET AL.							
Notice of Allowability	Examiner	Art Unit							
	BRET CHEN	1715							
All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R	The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.								
1. \square This communication is responsive to <u>9/6/12</u> .	1. 🛛 This communication is responsive to <u>9/6/12</u> .								
 An election was made by the applicant in response to a restriction requirement set forth during the interview on; the restriction requirement and election have been incorporated into this action. 									
3. ⊠ The allowed claim(s) is/are <u>1-10</u> .									
 4. ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have been received. 2. ☐ Certified copies of the priority documents have been received in Application No 									
3. Copies of the certified copies of the priority do	cuments have been received in this	national stage applica	tion from the						
International Bureau (PCT Rule 17.2(a)).									
* Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.									
	5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.								
 6. □ CORRECTED DRAWINGS (as "replacement sheets") mus (a) □ including changes required by the Notice of Draftspers 1) □ hereto or 2) □ to Paper No./Mail Date 	son's Patent Drawing Review(PTO	948) attached							
(b) ☐ including changes required by the attached Examiner' Paper No./Mail Date		Office action of							
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on the drawi he header according to 37 CFR 1.121(ngs in the front (not the d).	e back) of						
7. DEPOSIT OF and/or INFORMATION about the deposit of E attached Examiner's comment regarding REQUIREMENT FC									
 Attachment(s) 1. ⊠ Notice of References Cited (PTO-892) 2. □ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ⊠ Information Disclosure Statements (PTO/SB/08), 	5. ☐ Notice of Informal F 6. ☐ Interview Summary Paper No./Mail Da 7. ☐ Examiner's Amendi	(PTO-413), te							
Paper No./Mail Date <u>9/6/12, 3/15/12</u> 4.			wance						
 4. □ Examiner's Comment Regarding Requirement for Deposit of Biological Material 8. ☑ Examiner's Statement of Reasons for Allowance 9. □ Other 									
/Bret Chen/ Primary Examiner, Art Unit 1715									
U.S. Patent and Trademark Office PTOL-37 (Rev. 03-11)	otice of Allowability	Part of Paper No./N	/lail Date 20120926						

REASONS FOR ALLOWANCE

The following is an examiner's statement of reasons for allowance:

It is well known to form a metal oxide by ALD as noted by Aarik et al. (Thin Solid Films article). With respect to the precursor, it is well known to utilize metal alkylamide to form an oxide film by CVD as noted in Vaarstra (6,159,855). Furthermore, it is well known to utilize metal alkylamide to form a titanium-silicon-nitride film by ALD (Applied Physics Letters article). However, the prior art references fail to teach or suggest using alkylamide to form a metal oxide film by ALD.

Any comments considered necessary by applicant must be submitted no later than the

payment of the issue fee and, to avoid processing delays, should preferably accompany the issue

fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for

Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to BRET CHEN whose telephone number is (571)272-1417. The examiner can normally be reached on 7:30am - 4:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Timothy Meeks can be reached on (571) 272-1423. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Bret Chen/ Primary Examiner, Art Unit 1715 9/26/12

Notice of References Cited	Application/Control No. 12/407,556	Applicant(s)/Patent Under Reexamination GORDON ET AL.	
Notice of Melerences Cited	Examiner	Art Unit	
	BRET CHEN	1715	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	А	US-2006/0258078	11-2006	Lee et al.	438/216
	В	US-			
	С	US-			
	D	US-			
	Е	US-			
	F	US-			
	G	US-			
	Н	US-			
	Ι	US-			
	J	US-			
	К	US-			
	L	US-			
	М	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	Ν					
	0					
	Р					
	Q					
	R					
	s					
	т					

	NON-PATENT DOCUMENTS					
*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)				
	U	Min, Jae-Sik, et al., "Metal-organic atomic-layer deposition of titanium-silicon-nitride films". Applied Physics Letters, Volume 75, Number 11, 13 September 1999, pp.1521-1523.				
	v	Hausmann, Dennis M., et al., "Atomic Layer Deposition of Hafnium and Zirconium Oxides Using Metal Amide Precursors". Chem. Mater. Vol.14, No.10, 2002, 4350-4358.				
	w	Leskela, Markku, et al., "Review: Atomic layer deposition (ALD): from precursors to thin film structures." Thin Solid Films 409 (2002), pp.138-146.				
	x					

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).) Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

U.S. Patent and Trademark Office PTO-892 (Rev. 01-2001)

Notice of References Cited

Part of Paper No. 20120926

Receipt date: 09/06/2012

PTO/SB/C6a (07:09) Approved for use through 07/31/2012, OMB 0681-0081

U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE	ġ.,
Under the Parameter Beduction Act of 1995, no excesses are received to excession to a collection of information unless it contains a valid CMB control number	

Sut	silaute for foirs 1449/PTO			Complete if Known		
				Application Number	12/407,556-Conf. #7572	
IN	FORMATION	I DI	SCLOSURE	Fising Date	March 19, 2009	
l s	TATEMENT E	3Y /	APPLICANT	First Named Inventor	Roy G. GORDON	
				Art (kot	1715	
	(Usə əs many sh	eets as	i necessary)	Examine: Name	8, P. Chen	
Sheet	1	of	2	Attomey Docket Number	0042697.00135US7 (HU 1824)	

	U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No.	Document Number Number-Kind Cose ^{2 (d known)}	Publication Date MM-DD-YYYY	Name of Petentee or Applicant of Oited Document	Pages, Columne, Lines, Where Relevant Passages of Relevant Figures Appear		
••••••	AA*	US-6,359,160	03-19-2002	Son et al.			
·····							
÷	<u> </u>						

	FOREIGN PATENT DOCUMENTS							
Examiner Inivals*	Cite No. ¹	Foreign Patent Document - Country Code [®] -thimber [®] Kind Chiefe [®] (Foreien)	Publication Date MRA-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Unes, Where Polevant Persages Or Relevant Figures Appear			
	l		[]					
Signature		/Bret Chen/		Considered	09/25/2012			

"EXAMINER: initial if reference considered, whether sriver obtication is in conformance with MPEP 608. Draw line through citation if not in conformance and not considered, include copy of hits form with next communication to applicant. " CITE NOL: Those application(s) which are marked with an single asterisk (1) next to the Cite No, are not surplied funder ST CITE 1.9K(a/2)(iii) because that application was fixed after June 30, 2010 or is available in the FW. " Applicant's unique clation designation number (optimal). "See Kinds Code of USPTO Patient Documents of <u>wine years</u> or MPEP 901.04. "Enter Office that issued to descend to the senter more application must be reader to the class of USPTO Patient Documents, the indication of the year of the region must pracede the senter monte content of the patient document. " Kind of document by the appropriate symbols an indicate of the senter wife'O Standard ST.16 if possible." Applicant is to place a check mark here if English language Translation is attached.

ACTIVEUS 190827406v2 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./

PTO/SERGE: ((17.08) Adomited for use (hrough 07/31/2012: OMB 9861-0031 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under the Papersonk Reduction Act of 1996; no persone are required to respond to a collection of information unless if contains a valid ONB control number.

F	ubstitute for form 1449/PTO		Complete if Known		
-			Application Number	12/407,556-Conf. #7572	
INFORMATION DISCLOSURE			Filing Date	March 19, 2009	
-	STATEMENT I	3Y APPLICANT	First Naroud Investor	Roy G. GORDON	
		An Unit	1715		
(Use as many sheels as necessary)		Examiner Name	B: P. Chen		
Shee	i 2	of 2	Attorney Dockst Number	0042697.00135US7 (HU 1824)	

Examiner Initials	Cite No. ³	include name of the author (in CAPITAL LETTERS the item (book, magazine, journal, senal, symposic number(s), publisher, city and/c	um, catalog, stc.), date, page(s)		a ∂				
	CA	Chiu, "Chemical Vapor Deposition 803," Kirk-Oth Vol. 5, July 2004, pp. 803-813	mer Encyclopedia of Chen	nical Technology,					
	CB	Choy, "Chemical Vapour Deposition of Coatings," Progress in Materials Science, 48, 2003, pp. 57-170							
	cc	Condorelli et al., "Engineering of Molecular Architectures of 6-diketonate Precursors Toward New Advanced Materials," Science Direct, Coordination Chemistry Reviews, 251, 2007, pp. 1931-1950							
	CD	McElwee-White, "Design of Precursors for the C\ 2006, pp. 5327-5333	/D of inorganic Thin Films,	" Dalton Trans.,					
					<u> </u>				
Examiner Sidnature		/Bret Chen/	Date Considered	09/25/2012					

*EXAMINER, install if reference considered, whether or not citation is in nonhimitence with MPEP 609. Draw line birough citation if not in conformance and not considered, include copy of this form with next commissionation to applicant.

³Applicant's whipe plation designation number (optione). ³Applicant is to place a check mark here if English language Translation is attached.

ACTIVEUS 100827408v2 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./

	Application/Control No.	Applicant(s)/Patent Under Reexamination
Search Notes	12407556	GORDON ET AL.
	Examiner	Art Unit
	BRET CHEN	1715

SEARCHED						
Class	Subclass	Date	Examiner			
427	255.31, 255.36	3/15/2012	bc			
117	84, 88	3/15/2012	bc			
updated	previous	9/25/2012	bc			

SEARCH NOTES					
Search Notes	Date	Examiner			
east, google, inventor	3/15/2012	bc			
referred to related applications 11/199032, 10/381628	3/15/2012	bc			
east, google	9/25/2012	bc			

INTERFERENCE SEARCH					
Class	Subclass	Date	Examiner		
427	255.31, 255.36	9/25/2012	bc		
117	84, 88	9/25/2012	bc		

. г	

U.S. Patent and Trademark Office

Part of Paper No. : 20120926

	Inc	lex of (Claim	าร		oplication	(Con	trol N	10.	Applic Reexa	mina	ation	tent Unde	r	
												_ 1 7 (
					E)	aminer				Art Un	it				
					BF	RET CHEN	l			1715	1715				
✓	R	ejected		-	Car	Cancelled N			Non-Elected		A		Арр	peal	
=	Δ	llowed		÷	Res	tricted		I	Interference			0	Obje	Objected	
⊠ c	laims r	enumbered	in the s	ame c	order as pr	esented by a	applic	ant	C] СРА	C] т.с). 🗆	R.1.47	
	CLA	M							DATE						
Final		Original	01/06/2	012 0	03/15/2012	09/25/2012									
		1	÷		\checkmark	=									
		2	÷		~	=									
		3	÷		~	=									
		4	÷		~	=									
		5	÷		~	=									
		6	÷		~	=									
		7	÷		\checkmark	=									
		8	÷		~	=									
		9	÷		~	=									
		10	÷		~	=									
		11	÷		-	-									
		12	÷		-	-									
		13	÷		-	-									
		14	÷		-	-									
		15	÷		-	-									
		16	÷		-	-									
		17	÷		-	-									
		18	÷		-	-									
		19	÷		-	-									

U.S. Patent and Trademark Office

20

÷

-

-

Part of Paper No. : 20120926

	Application/Control No.	Applicant(s)/Patent Under Reexamination
Issue Classification	12407556	GORDON ET AL.
	Examiner	Art Unit
	BRET CHEN	1715

	ORIGINAL INTERNA								INTERNATIONAL	CLA	SSI	FIC	ΑΤΙ	ON	
	CLASS			SUBCLASS		CLAIMED						NON-CLAIMED			
427			255.31			С	2	3	С	16 / 40 (2006.01.01)					
	CR	OSS REFI	ERENCE(S)											
CLASS					CK)										
427	255.36														
117	84	88													

⊠	Claims re	numbere	d in the s	ame orde	r as prese	ented by a	pplicant		CP] T.D.	0] R.1.	47	
Final	Original	Final	Original	Final	Original	Final	Original	Final	Original	Final	Original	Final	Original	Final	Original

NONE		Total Clain	ns Allowed:
(Assistant Examiner)	(Date)	1	0
/BRET CHEN/ Primary Examiner.Art Unit 1715	9/26/12	O.G. Print Claim(s)	O.G. Print Figure
(Primary Examiner)	(Date)	1	none

U.S. Patent and Trademark Office

Part of Paper No. 20120926

Signature

PTO/SB/06a (07:09) Approved for use through 07/31/2012, OMB 0661-0061

 - 0.5, Passre and 1 	nademaax Omce; i	15. OF 84831	MENT OF COMMERCE.
the second second second second second	1. A. M. 1. 1. 1. 1. 1. 1. 1. 1. 1. 1. 1. 1. 1.		in the second second second second second second

{	<u>Paperwork Hedi</u> for foire 1449/		195, no persone are recipired to	3	nation unless it contains a velid CMB control number. Complete if Known
				Application Number	12/407,556-Conf. #7572
INFC	RMATI	ION DI	SCLOSURE	Filing Date	March 19, 2009
STA	STATEMENT BY APPLICANT		VPPLICANT	First Named Inventor	Roy G. GORDON
				Art Unst	1715
	(Use as mar	ry sheets as	necessary)	Exatoine: Naroe	B. P. Chen
Sheet	1	Gf	10	Attomey Docket Number	0042697.00135US7

			U.S. PA	TENT DOCUMENTS	
Ezaminar Initisla*	Cite No.	Elocament Number Number-Kind Cose ^{2 (1/ known)}	Publication Date MM-DD-YYYY	Name of Patemee or Applicant of Oited Document	Pages, Columis, Lines, Wiere Relevant Passagus of Relevant Figures Appear
	AA*	US-2001/0054769	12-27-2001	Raaijmakers et al.	
	A8*	US-2002/0004281-A1	01-10-2002	Lee et al.	
	AC*	US-2002/0018849-A1	02-14-2002	George et al.	
	AO*	US-2002/0102814-A1	08-01-2002	Olsen	
	AE'	US-2003/0015764-A1	01-23-2003	Raajimakers et al.	
	AF*	US-2003/0129087	07-10-2003	Barbee et al.	
	AG*	US-2004/0018694-A1	01-29-2002	Lee et al.	
	AH*	US-2005/0065358	03-24-2005	Itsuki et al.	
	AI*	US-2006/0046426	03-02-2006	Sandhu et al.	
	AJ*	US-2006/0046518	03-02-2006	Hill et al.	
	AK*	US-2006/0062910	03-23-2006	Meiere	
	AL*	US-2006/0110936	05-25-2006	Hilletal.	
	AM*	US-2006/0246719	11-02-2006	Rueger et al.	
	AN*	US-2007/0180761	07-12-2007	Reuter et al.	
	AO*	US-4,386,117	05-31-1983	Gardon	
	AP*	US-4,474,642	10-02-1984	Nakane et al.	
	AQ*	US-4,512,862	04-23-1985	Rigby	
	AR*	US-4,723,978	02-09-1988	Clodgo et sit.	
	AS*	US-4,792,463	12-20-1988	Okada et al.	

Examinar Initials*	Cite No."	Foreign Potent Document - Country Code ² -Number ⁴ Kind Code ² (/ Jacobs)	Publication Date MM-OD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Unes, Where Polevant Persages Or Relevant Figures Appear	$\mathbf{J}_{\mathbf{s}}$
	8 <u>A**</u>	DE-43 16 883-A	11-24-1994	Denk, Michael Dr.		$\overline{\mathbf{v}}$
	88**	EP-0 560 617-A	09-15-1993	Kawasaki Steel Co.		<u> </u>
	80**	EP-1067595-A2	01-10-2001	Air Products and Chemicals Inc.		
	80**	JP-04359515	12-11-1992	NEC Corp		V
	BE	JP-06140390-A	05-20-1994	Kawasaki Steel Corp.		V
	BF	JP-07153696-A	06-16-1995	Canon Sales Co., Inc.		$\overline{\langle}$

*EXAMINER: Initial 8 reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation # not in conformance and not considered. Include copy of this form with next communication to applicant. * CITE NO: These application(s) which are marked with an single astarisk (*) next to the Cite No: are not supplied for with next communication to applicant. * CITE NO: These application(s) which are marked with an single astarisk (*) next to the Cite No: are not supplied for with next communication to applicant. a CITE NO: These application(s) which are marked with an single astarisk (*) next to the Cite No: are not supplied for an entry of the PW, ** CITE NO: These document(s) which are marked with an obub eaterisk (*) in text to the Cite No: are not supplied for an entry interview of a supplication relied upon in this application for an earlier filing data index 35 U.S.C. 120. * Applicant's unique chatter designation number (obtional). * See Kinds Codes of UEPTO Patent Documents at <u>market upon of the PP</u> 901.01. * Enter Office that issued the document, by the approximate documents, the indication of the year of the regin of the Emperer must proceed the section number (OVPO Standard ST.18 F possible, * Applicant is to place a check new to the code of Social Articles as indicated on the document under WPO Standard ST.18 F possible, * Applicant is to place a check new to be code of social codes of the code of document. mark here if English language Trunslation is attached.

ACTIVEUS #9900329941 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./

Considered

09/25/2012

Signature

PTO/S&/66a (07-09) Approved for use through 07/31/2012, OMB 9861-0681

U.S. Paterit and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Substitute	dor tom 1449/P	10		Complete if Known					
				Application Number	12/407,556-Conf. #7572				
INFC	RMATI	ON DIS	CLOSURE	Filing Date	March 19, 2009				
STATEMENT BY APPLICANT				First Named Inventor	Roy G. GORDON				
				Ast Unit	1715				
(Use as many sheets as necessary)				Examiner Name	B. P. Chen				
est	2	of	10	Attorney Docket Number	0042697.00135US7				

Exansinar Inišals'	Cite No.]	Document Number Number-Kind Code ^{y (193} 00en)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, When Relevant Passages or Relevan Figures Appear
	AT*	US-5,064,686	11-12-1991	McGeary	
	AU*	US-5,389.401	02-14-1995	Gordon	
	AV*	US-5,403,630	04-04-1995	Matsui et al.	
	AW*	US-5,710,075	01-20-1998	Tseng	
	AX*	US-5,922,787	07-13-1999		
	AY*	US-6,090,442	07-18-2000	Kiaus et al.	
	AZ*	US-6,203,613	03-20-2001	Gates et al.	
	AAI*	US-6,258,707	07-10-2001	Uzoh	
	AB1	US-6,335,288	01-01-2002	Kwan et al.	
	AC1*	US-6,339,004	01-15-2002	Kim	
	AD1*	US-6,342,432	01-29-2002	Wang	
	AE1*	US-6,395,209-A1	05-28-2002	Yoshida et al.	
	AF 1*	US-6,482,733	11-19-2002	Raaijmakers et al.	
	AG1*	US-6,534,395-A1	03-18-2003	Werkhoven et al.	}
	AH1*	US-6,867,152	03-15-2005	Hausmann et al.	
	AIT	US-6.949,269	09-27-2005	Seidt et al.	
	AJ1*	US-6,969,539-A1	11-29-2005	Gordon et al.	
	AK1*	US-7,064,227		Lei et al.	
	TAL 1º	US-7.097,878	08-29-2006	Rulkens et al.	

		FOREI	GN PATENT	DOCUMENTS		
Exaroiner hitialer	Cite No. ⁴	Fontign Patent Document Country Code" -Nortber"-Mint Code" (# known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pisges, Columns, Lines, Where Relevant Passages Or Relevant Pignars Appear	Ţ
	8G	JP-2001-074931-A	03-23-2001	Nippon Kogaku KK		N V
	8H**	JP-2002-093803-A2	03-29-2002	Machida et al.		1
	81**	JP-2002-093804-A2	03-29-2002	Tri Chemical Labatory Inc.		
	BJ	JP-3177560-A	08-01-1991	Nippon Steel Corp; Matsushita Electric Ind Co Ltd		5
	8K**	JP-3409290	05-28-2003	Tri Chemical Laboratories, Inc.		
	8L**	KP-10-2005-0039421	04-29-2005	Samsung Electronics Co., Ltd.		Γ,

*EXAMINER: Initial if infertence considered, whether or not obtained is in conformance with MPEP 605. Craw line through obtain it not in conformance and not considered. Include copy of this form with next communication to application. * OTE NOL: These applications is whether are not supplied tunker b? CER 1.96(a)(2)(i) because that explained in was filed after one 30, 2013 or is evaluate in the IPW, ** OTE NOL. These applications is whether are not supplied tunker b? CER 1.96(a)(2)(ii) because that explained reading was filed after one 30, 2013 or is evaluate in the IPW, ** OTE NOL. These documenting which are marked with an abulic extensity (*) next to supplied because they are not supplied because they are provided by or the IPW, ** OTE NOL. These documenting which are marked with an double entered (*) next to supplied because they are provided by or to the IPW, ** OTE NOL. These documenting which are marked with an double entered (*) next to supplied because they are provided by or to the IPW, ** OTE NOL. These documenting which are marked with an enterman double entered (*) next to the CBN Nor are not supplied because they are provided by or to the other interest to a serier filling date under 35 U.S.C. 120. * Applicant's unique clation designation number (optional), *see Ninds Codes of USPTIC Paterel Documents at <u>serve supplication of the WHEP</u> Standard ST.M. *For Japanese pater information, the indicated on the document where WIPO Standard ST.S. # possible. * Applicant et to place a check mark here # English language Translation is attested.

ACTIVEUS #990 2001 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./

PTO/SB/08a (07:08) Approved for use through 07/31/2012, OMB 0661-0631 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1996, no persons are required to respond to a collection of information unkers it contains a valid CMB control number

- Substitute for form 1449/PTO	Complete if Known		
	Application Nomber	12/407,556-Conf. #7572	
INFORMATION DISCLOSURE	Filing Date	March 19, 2009	
STATEMENT BY APPLICANT	First Named Inventor	Roy G. GORDON	
	Art Unit	1715	
(Use as many sheats as necessary)	Examiner Name	B, P, Chen	
Shest 3 of 10	Attorney Docket Number	0042697.00135US7	

			U.S. PA	TENT DOCUMENTS	
Exaroiner Inišels'	Cits No.]	Document Number Number-Kind Code ^{2 (18 known)}	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Peges, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	AM1*	US-7,109,129	09-19-2006	Papasouliotis	
	AN1*	US-7,129,189	10-31-2006	Hausmann et al.	
	AO1*	US-7,135,418	11-14-2006	Papasouliolis	
	AP1*	US-7,148,155	12-12-2006	Tarafdar et al.	
	AQ1*	US-7,157,385	01-02-2007	Derderian et al.	
			01-16-2007	Cho et al.	
	AS1*	US-7,507,848	03-24-2009	Gordon et al.	
	ļ				
	ļ				
	ļ				
	Į				
	Ļ				
	ļ				
	Ļ				
	ļ				
			<u></u>		
	Ļ				
1	1		{		

Examinar	Cite	Foreign Patent Document	Publication	Name of Patenteelin	Pages, Columns, Lines, Where Relevant Passages	
wials"	No.4	Country Code? - Nonsber? Wind Code? (8 Incomp	MM-DD-YYYY	Applicant of Cited Document	Cr Relevent Pignaes Appear	1
	BM**	KR-156980-A2	07-27-1998	Hyun Joo Shin		1
	8N**	WO-00/16377-A2	03-23-2000	Gentiech Co., Ltd.		Γ
	80**	WO-01/27347	04-19-2001	ASM Microchemistry OY		1
	8P**	WO-01/45158-A1	06-21-2001	Genus, Inc.		Ĩ
	8Q**	WO-02/27063-A2	04-04-2002	President and Fellos of Harvard College		-
	BR	WO-2003/983167	10-09-2003	President and Fellows of Harvard College		

*EXAMINER: Initial 8 reference considered, whether to not obtain is in conformance with MPEP 609. Draw line through obtain if not in conformance and not considered. Include copy of this form with next communication to applicant, * CITE NOL. These applications is this after June 10, 2000 or is available in the FWL. ** OTE NOL. These document(s) which are not supplied (under 37 CER 1.346)(22(6)) because that application was filed after June 10, 2000 or is available in the FWL. ** OTE NOL. These document(s) which are marked with an device asther (*) sents the CER No. are not supplied because they were previously olded by or submitted to the Office in a prior application relied upon in this application for an earlier filing date under 35 U.S.C. 120. ** Applicants unique chafter during the built office in a prior application relied upon in this application for an earlier filing date under 35 U.S.C. 120. ** Applicants unique chafter during the built diffice in a prior application relied upon in this application for an earlier filing date under 35 U.S.C. 120. ** Applicants unique chafter during (wFPO Standers ST.3). ** For department part <u>appropriate astrone</u> to <u>available or under ST</u> Standerd ST.16 if possible. ** Applicant is to place a check mark here if English language Translation is attached.

ACTIVEUS \$7555525541 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./

PTO/SEVCEa (07:03) Approved for use through 07/31/2012, OMB 9661-0031

U.S. Paters and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under the Paperwork Reduction Act of 1995, no persone are required to reasond to a objection of information unless it of s à valid OMB ion nerest mer

Sui	vsitule for form 1449/PTO				Complete # Known
				Application Nomber	12/407,556-Conf. #7572
11	IFORMATION DISCLOSURI	SCLOSURE	Filing Date	March 19, 2009	
S	STATEMENT BY APPLICANT		APPLICANT	First Named Inventor	Roy G. GORDON
				Ast Unit	1715
	(Use as many sh	eets av	i necessary)	Examiner Name	B, P, Chen
Shest	4	হা	10	Attorney Docker Number	0042697.00135US7

			U.S. PA	TENT DOCUMENTS	
Examiner Initiale'	Cite No.]	Document Number Number-Kiné Code ^{21 (#3acoun)}	Publiciation Date MM-DD-YYYY	Name of Patentee or Applicant of Clad Document	Pages, Columna, Lines, Where Relevant Passages or Relevant Figures Appear
					+
·····					

		·			

Examinar	035	Foreign Patent Document	Publication	Niterrija p	n Patentec ior	Pages, Columns, Lines,	Γ
hitiste"	Cite No.	Country Code" -Romber ¹ Word Code ¹ (Known)	Date MM-DD-YYYY		f Cited Document	Whene Relevant Passages Or Relevant Figures Appear	ŗ
	85**	WO-91/08322-A1	06-13-1991	President an Harvard Coll			
	81**	WO-97/38355	10-16-1997	Micrion Corp	U.		ſ
	80**	WO-98/15669-A	04-16-1998	Feits, John T	x Y		1
	8V**	WO-99/29924-A	06-17-1999	Neste OYJ e	t al.		[
	8W**	WO-99/29926-A	06-17-1999	Siemens AG Materials	; Advanced Tec	h	-
	[Ľ
Examiner Signature	3	/Bret Chen/		******************************	Date Considerent	09/25/2012	,000

"EXAMINER: Initial if inference considered, whether or not obtailed is is nonliminance with MPEP 608. One implement if not in contiminance and not considered. Inducts copy of the form with next communication to applicant. " CITE NO... Those applications is whether is nonliminance and not considered. Inducts copy of the form with next communication to application was fixed after June 50, 2003 or is evaluable in the FW, " CITE NO... Those applications is in containing which are marked with an engine seterate (1) next to the CBe No. are not supplied to the FW, " CITE NO... Those applications is in containing which are marked with an engine seterate (2) next to the CBe No. are not supplied to the FW, " CITE NO... These documentity which are marked with an explicit settation of the CIEe No. are not supplied to the rest provided by an excercit the two submitted to the CIEe No. are not supplied to the FW, " CITE NO... These documentity which are marked with an explication for an earlier sting date under 35 U.S.C. 120..." Applicant's unique clation designation number oblematic "see Kinds Codes of DSPTIO Patent Documents at <u>server sectors of the PEP KI1 AL</u>. " Enver Online that issued the stress in universe of the patent optional..." For lapances patent documents, the indicated on the document under WIPO Standard ST.15 If possible. ⁸ Applicant is to place a check mark here it English language Translation is attended.

ACTIVEUS \$9368326641 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./

Examiner

Signature

09/25/2012

PTO/SERGE: ((17.08) Adomited for use (hrough 07/31/2012: OMB 9861-0031 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under the Papersonk Reduction Act of 1996; no persone are required to respond to a collection of information unless if contains a valid ONB control number.

Substitute for form 1449/PTO		Complete II Known
	Application Number	12/407,556-Conf, #7572
INFORMATION DISCLOSURE	Filing Date	March 19, 2009
STATEMENT BY APPLICANT	First Naroed Inventor	Roy G. GORDON
	An Unir	1715
(Use as many sheets as necessary)	Examiner Name	B. P. Chen
Sheet 5 of 10	Attorney Docket Number	0042697.00135US7

Examiner Initials	Cite No.1	include name of the author (in CAPTIAL LETTERS), take of the article (when appropriate), lifte of the item (book, magazine, journel, senel, symposium, catalog, str.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	r
	CA**	"Table 36 DRAM Trench Capacitor Films Technology Requirements." (2000), 1 Page.	
	C8**	Backer et al., "Esters Mixtes De L'Acide Tetrathic Orthosilicique", Rev. Trav. Chim., Vol. 61, pp. 500-512, 1942	
	cc	Becker, et al., "Diffusion Barrier Properties of Tungsten Nitride Films Grown by Atomic Layer Deposition from bix(tert-butylimido)bis(dimethylamido)lungsten and ammonia," Applied Physics Letters, Vol. 82, No. 14, April 2003, pp. 2239-2241	
	CD**	Bergstrom et al. "Molecular Descriptors influencing Meiling Point and Their Role in Classification of Solid Drugs" J. Chem. Inf. Comput. Sci. 2003, 43, 1177-1185	
	CE**	Bradley et al., "Metallo-organic Compounds Containing Metal-Nilrogen Bonds. Part VI Infrared and Nuclear Magnetic Resonance of Dialkylamido-derivatives of Titanium, Vanadium, Ziropnium Nicibium, Hafnium, Tantalum, and Thonium", J. Chem. Soc., A., pp. 980-984, 1969	
	CF	Bradley, et al., "Metallo-organic Compounds containing Metal-Nilrogen bonds. Part I. Some Dialkylamino-derivatives of Tilanium and Zirconium," J. Amer. Chem. Soc., 1955, 77, pp. 3857-3861	
	CG**	Chang, J.P. and LIN, Y.S. "Thermal stability of stacked high-k dielectrics on silicon" Applied Physics Lettes, Vol. 79, No. 23, 3 December 2001 (3824-3826)	
	Сн**	Coltrin, M. et al., "Chemical kinetics in chemical vapor deposition: growth of silicon dioxide from tetraethoxysilane (TEOS)", <i>Thin Solid Films, Elsevier-Seguola S.A., Lausanne, Ch</i> , Vol. 365, No. 2, pp. 251-263, XP004197205, ISSN: 0040-6090, April 2000	

"EXAMINER: Initial if reference considered, whether or not abation is in conformance with MPEP 605. Drew line through abation if not in conformance end not considered. Include copy of this form with next communication to applicant. "" CITE NOL Those document(s) which are marked with an double esteries (") want to the CBs flow are not complied because they were previously abad by or submitted to the Office in a polar spokration telled upon in this spokration for an earlier thing date under 35 U.S.C. 120.

Date

Considerat

Applicants uninte station designation number (optional). "Applicant is in place a check mark here if English language Translation is attached.

/Bret Chen/

ACTIVEUS \$755555551 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./

Signature

09/25/2012

Considered

PTO/SERGE: ((17.08) Adomited for use (hrough 07/31/2012: OMB 9861-0031 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under the Papersonk Reduction Act of 1996; no persone are required to respond to a collection of information unless if contains a valid ONB control number.

Substi	tute for form 1449/PTO			Complete if Known
			Application Number	12/407,556-Conf. #7572
INF	INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Filing Date	March 19, 2009
ST ST			First Named Inventor	Roy G. GORDON
			Anthà	1715
	(Use as many sh	sets as necessary)	Examiner Name	B. P. Chen
Sheet	6	of 10	Attornéy Docket Number	0042697.00135US7

Examiņar Initiāls	Cile No.'	Include name of the author (in CAPITAL LETTERS), title of the anticle (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, pege(s), volume-issue number(s), publisher, city and/or country where published.	T
	CI	European Search Report issued for European Patent Application No. EP 06026277, dated February 27, 2007, 2 pages	
	CJ**	Ferguson et al., "Atomic Layer Deposition of A12O3 and StO2 on BN Particles using Sequential Surface Reactions", <i>Applied Surface Science</i> , Vols. 162-163, pp. 280-292, 2000	
	СК**	Ferguson et al., "Atomic Layer Deposition of SiO2 Films on BN Particles using Sequential Surface Reactions", <i>Chem. Mater,</i> Vol. 12, pp. 3472-3480, 2000	
	ce*	Fix, R. et al., "Chemical Vapor Deposition of Titanium, Ziroonium, and Hafnium Niirlde Thin Films," Chemistry of Materials 3(1991) Nov./Dec., No. 6, Washington, DC, US, pp. 1138-1148	
	CM**	Furumura, Y. Abstract for "High-K dielectrics for DRAM applications" (1996), 1 Page.	
	CN**	Gasser et al., "Quasi-Monolayer Deposition of Silicon Dioxide", <i>Thin Solid Films</i> , Vol. 250, pp. 213-218, 1994	
	CO**	George et al., "Atomic Layer Controlled Deposition of SiO2 and Al2O3 Using ABABbinary reaction sequence chemistry", <i>Appl. Surf. Sci.</i> , 82/83, pp. 460-467, 1994	
	ĊP	Gordon et al., "Vapor Deposition of Metai Oxides and Silicates: Possible Gate Insulators for Future Microsfectronics," Chem. Mater., 2001, 13, pp. 2463-2464	
	cq	Haukka, et al., "Chemisorption of chromium acetylacetonate on porous high surface area silica," Applied Surface Science 75, 1994, 220-227, 8 pages	

"EXAMINIER: Initial 3 esterance considered, whether or not obtain is in conformance with MPEP 605. Draw line through obtains 3 not in conformance and not considered. Include copy of this form with next communication to applicant. " CIYE NOL Those documentia; which are marked with an double esterisk (") next to the Cite No, are not supplied because they were previously ofted by or submitted to the Office in a prior application relied upon in the application for an earlier filing date under 05 U.S.C. 121.

"Applicants unique obtains designation number (options); "Applicant is to place a check mark here if English language Translation is attached.

/Bret Chen/

HARVARD Ex. 2117, p.18

Examiner

PTO/SERGE: ((17.08) Adomited for use (hrough 07/31/2012: OMB 9861-0031 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under the Papersonk Reduction Act of 1996; no persone are required to respond to a collection of information unless if contains a valid ONB control number.

Bubstitute for form 1443/PTO		Complete if Known
	Application Number	12/407,556-Conf. #7572
INFORMATION DISCLOSURE	Filing Date	March 19, 2009
STATEMENT BY APPLICANT	Past Named Inventor	Roy G. GORDON
	An Unit	1715
(Use as many sheets as necessary)	Examiner Name	B. P. Chen
Sheet 7 of 10	Attomey Docket Number	0042697.00135US7

Examinar Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), tille of the article (when appropriate), tille of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, pegs(s), volume-issue number(s), publisher, only and/or country where published.	T
	CR**	Hausmann et al., "Rapid Vapor Deposition of Highly Conformal Silica Nanolaminates", Science, Vol. 298, op. 402-406, 2002	
	CS**	Hausmann et al. "Atomic Layer Deposition of Hafnium and Zirconium Oxides Using Melal Amide Precursors" Chem. Mater. 2002, 14, 4350-4358	
	CT**	Hughes et al. "Why are some properties more difficult to predict than others? A study of QSPR models of solubility, melting point, and Log P" J. Chem. Inf. Model, 2008, 48, 220-232	
	cu**	Ikeda, Y. et al., "Ozorie/Organio-Source APCVD for ULSI Reflow Glass Films: NEC Research and Development, Nippon Electric, Ltd., No. 94, pp. 1-7, XP000067542, ISSN: 0547-051X, 1 July 1989	
	cv	International Search Report of the International Searching Authority, the European Patent Office, for International Application No. PCT/US03/09736, mailing date September 12, 2003, 7 pages, 3 pages	
	CW	International Search Report of the International Searching Authority, the European Patent Office, for PCT/US01/30507, mailing date August 19, 2002, 5 pages	
	сх**	Jeon et al. "Thermal stability of ultrathin ZrO ₂ films prepared by chemical vapor deposition on Si(100)" Applied Physics Letters, Vol. 78, No. 3, 15 January 2001 (368-370)	
	CY	Jones, et al., "MOCVD and ALD of High-k Dielectric Oxides Using Alkoxide Precursors," Chemical Vapor Deposition, 2006, 12, pp. 83-98	
	cz**	Kang et al. Abstract for "Electrical characteristics of highly reliable ultrathin hafnium oxide gate dielectric" (2000), 1 Page.	
	CA1**	Kang et al. Abstract for "Highly reliable thin hafnium oxide gate dielectric" (2000), 1 Page.	

/Bret Chen/ 09/25/2012 Signature Considered

Date

EXAMINER: Initial 3 reference considered, whether or not claston is in conformance with MPEP 000, Chaw line through claston if not in conformance and not considered. Include copy of the form with next communication to approach. " OTHE NCL: Those documential which are marked with an double setterak (**) next to the Cite No, are not supplied because bey were previously clied by or submitted to the Othice is a prior application relied upon in this application for an earlier filling date under 35 U.S.C. 120.

Applicant's unique citation designation number (optional). "Applicant is to place a shack mark here if English language Translation is altached.

ACTIVEUS \$755555551 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./

HARVARD Ex. 2117, p.19

PTO/SERGE: ((17.08) Adomited for use (hrough 07/31/2012: OMB 9861-0031 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under the Papersonk Reduction Act of 1996; no persone are required to respond to a collection of information unless if contains a valid ONB control number.

Bubstitute for form 1449/PTO	Complete If Known		
	Application Number	12/407,556-Conf. #7572	
INFORMATION DISCLOSURE	Filing Date	March 19, 2009	
STATEMENT BY APPLICANT	Past Named Inventor	Roy G. GORDON	
	An Unit	1715	
(Use as many sheets as necessary)	Examiner Name	B. P. Chen	
Sheet 8 of 10	Attomey Docket Number	0042697.00135US7	

Examiçar Initials	No.'	the item (book, magazine, journal, senal, symposium, catalog, etc.), dete, pege(s), volume-issue number(s), publisher, div and/or country where published.							
		Kingon et al., "Alternative dielectrics to silicon dioxide for memory and logic devices", Nature, Vol. 406, pp. 1032-1038, 2000							
		Klaus et al., "Atomic Layer Deposition of SiO2 al Room Temperature using NH3-catalyzed Sequential Surface Reactions", Surf. Sci., Vol. 447, pp. 61-90, 2000							
		Klaus et al., "Atomic Layer Deposition of SiO2 using Catalyzed and Uncatalyzed Self-Limiting Surface Reactions", <i>Surface Review and Letters</i> , Vol. 6, No. 3, pp. 435-448, 1999							
	CE1**	Lee et al. Abstract for "High-quality ultrathin CVD HfO2 gate stack with poly-Si gate electrode" (2000), 1 Page.							
	CF1**	Lee et al. Abstract for "Ultrathin hafnium oxide with low leakage and excellent reliability for alternative gate dielectric application," Technical Digest: International Electron Devices Meeting, 1999, 1 Page							
	CG1	Lee et al., "Mass Production Worthy HIO2 -AI2O3 Laminate Capacitor Technology using Hf Liquid Precursor for Sub-100nm DRAMS", <i>Presented at IEEE IEDM (International Electronic Devices Meeting)</i> , San Francisco, CA, 9-11 December 2002, 4 pages							
	СН1**	Leng et al. Abstract for "Rotating compensator spectroscopic ellipsometry (RCSE) and its application to high-k dielectric film HfO2," Proceedings of SPIE, 2008, 1 Page.							
	CI1**	McIvor et al., "Preparation and Toxicity of Some Alkyl Thiopyrophosphates", Canadian J. Chemistry, Vol. 34, pp. 1825-1827, 1956							
	Server 8	Min et al. "Atomic Layer Deposition of TiN Films by Alternate Supply of Tetrakis (ethylmethylamino)-Titanium and Ammonia" <i>J. Apol. Phys.</i> Vol. 37 (1998) 4999-5004							
	CK1**	Morishita et al., "New Substances for Atomic-Layer Deposition of Silicon Dioxide", J. Non- Crystalline Solids, Vol. 187, pp. 66-69, 1995							
Examiner Signature	2	/Bret Chen/	Date Considerad	09/25/2012					

*EXAMINEN: Initial Freference considered, whether or not station is in conformance with MPEP 60%. Craw the through dilation if not in conformance and not considered. Individe copy of this form with next communication to applicant. ** CITE NOL These document(s) which are marked with an double asterist (**) want to the CR4 Ro, we not samplied because they were previously offed by or submitted to the CR0.e in a prior spontation relied upon in the spontation for an easilier filling date under 35 U.S.C. 120.

Applicant's unknowniation designation number (optional). "Applicant is in place a check mark here it English language Translation is attached.

Examiner

Signature

09/25/2012

PTO/SERGE: ((17.08) Adomited for use (hrough 07/31/2012: OMB 9861-0031 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under the Papersonk Reduction Act of 1996; no persone are required to respond to a collection of information unless if contains a valid ONB control number.

Bubstitute for form 1449/PTO			Complete if Known		
			Application Number	12/407,556-Conf: #7572	
		Filing Date	March 19, 2009		
		VT I	First Named Inventor	Roy G. GORDON	
			An Unit	1715	
		Examiner Name	B. P. Chen		
She	et 9	of 10		Attomey Docket Number	0042697.00135US7

Examiçar Initials	Cite. No.1	include name of the author (in CAPITAL LETTERS), tille of the article (when appropriate), tille of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ^s	
	CL1**	Nugent et al., "Some Bis(<i>ferf-</i> butylimido) Complexes of the Group 6 Transition Metals and a Related Alkylamido Darivative.; <i>Inorg. Chem.</i> , Vol. 19, pp. 777-779, 1980		
	CM1**	Okamoto et al., "Convenient Synthetic Route to Mono-Or Dialkyl Phosphate from inorganix Phosphorus Acids", <i>Phosphorus, Sulfur and Silicon</i> , Vol. 55, pp. 195-200, 1991		
	CN1	Ott, et al., "Modification of Porous Alumina Membranes Using A12O3 Alomic Layer Controlled Deposition," Chem. Matter, 1997, 9, pp. 707-714, 8 pages		
	CO1	Park et al., "Mass-Productive Ultra-Low Temperature ALD SiO2 Process Promising for Sub 90nm Memory and Logic Devices", <i>Presented at IEEE IEDM (International Electronic Devices</i> Meeting), San Francisco, CA, 9-11 December 2002, 4 pages		
	CP1	Pouronen, "Surface Chemistry of Atomic Layer Deposition: A Case Study for the Trimethyaluminum/water Process," Journal of Applied Physics 97, 121301-1 – 121301-52, 2005		
	CQ1**	Qi et al. Abstract for "High-K gate dielectrics," Proceedings of SPIE, 1999, 1 Page.	Ĩ	
	CR1**			
	CS1**	Fitala, "Advanced ALE processes of amorphous and polycrystalline films", Applied Surface Science, Vol. 112, pp. 223-230, 1997		
	сти	Sun et al. "Interfacial silicon oxide formation during synthesis of ZrO ₂ on Si(100)" Applied Surface Science 161 (2000) 115-122		

*EXAMINER: Initial 3 reference considered, whether or not obston is is conformance with MPEP 609. Draw like through obston 3 not in conformance and not considered. Include copy of this form with next communication to applicant, "" CITE NOL. Those document(s) which are marked with an double adartisk ("") next to the Cite NoL are not supplied because they were providely obst by or submitted to the Office in a prior application relied upon in this application for an earlier filing date under 35 U.S.C. 120.

Oate

Considered

Applicants unique citation designation number (optional). Applicant is to place a check mark here if English language Travelation is attached.

/Bret Chen/

ACTIVEDS #393932859/1 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./

PTO/SERGE: ((17.08) Adomited for use (hrough 07/31/2012: OMB 9861-0031 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under the Papersonk Reduction Act of 1996; no persone are required to respond to a collection of information unless if contains a valid ONB control number.

Substitute for form 1443/PTO		Complete if Known			
			Application Number	12/407,556-Conf. #7572	
		Filing Date	March 19, 2009		
		First Named Inventor	Roy G. GORDON		
				Arthi	1715
	(Use as many sheets as necessary)		Examiner Name	B. P. Chen	
Sheet	10	of	10	Attorney Docket Number	0042697.00135US7

	Cite. No.1	Include name of the author (in CAPTIAL LETTERS), title of the anticle (when appropriate), title of the item (book, magazine, journal, senial, symposium, catalog, etc.), dete, page(s), volume-issue number(s), publisher, city and/or country where published.						
	cui	Sundermeyer, "Neue Organometall-Imide des Molybdans und Wolframs - die direkte Einfuhrung der Cyclopentadienyl-Gruppe durch Maskierung der hohen Oxidationsstufe," Chem. Ber., 124, 1991, pp. 1977-1979						
	CV1	Voronikov, et al., "Reaction of TRIS (Trimethylsiliyi) Phosphate with Salts of Inorganic and Organic Acids," UOS 542.91:547.1128118, 1 page, 1978						
		Yamaguchi et al., "Atomic-Layer Chemical-Vapor-Deposition of Silicon Dioxide Films with an Extremely Low Hydrogen Content", Applied Surface Science, Vols. 130-132, pp. 202-207, 1998						
	CX1**	Zwierzak et al., "Organophosphorus Esters - I-Butyl As Protecting Group tin Phosphorylation via Nucleophilic Displacement", <i>Tetrahedron</i> , Vol. 27, pp. 3163-3170, 1971						
Examiner	·	/Bret Chen/	IDate I					

*EXAMPLER: Initial Freference considered, whether or not station is in conformance with MPEP 606. Drew line through station if not in conformance and not considered. Inducte copy of this form with next communication to applicant. ** CITE NOL These document(s) which are marked with an out-ble asterisk (**) must to the CR4 R0, are not supplied because they were previously sted by or submitted in the Office in a policitation relied upon in the application for an earlier filling date under 35 U.S.C. 100.

"Applicant's unique station designation number (optional). "Applicant is to place a check mark here it English language Translation is attached...

HARVARD Ex. 2117, p.22

ACTIVEUS \$755555551 ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /B.C./